L Number	Hits	Search Text	DB	Time stamp
1	11875		USPAT;	2004/09/30 15:14
		resist) resist) near10 (etch\$3 pattern4 trim\$4 remov\$3) near10 dry	US-PGPUB	
2	3636		USPAT;	2004/09/30 15:12
_	0000	resist) resist) near10 (etch\$3 pattern4	US-PGPUB	=====================================
		trim\$4 remov\$3) near10 dry ) and		
		((hydrocarbon CH4 ("CH.sub.4")) and argon		
		and oxygen "0.sub.2")		
3	2	, . <u></u>	USPAT;	2004/09/30 15:08
		resist) resist) near10 (etch\$3 pattern4	US-PGPUB	
		trim\$4 remov\$3) near10 dry ) and		
		((hydrocarbon CH4 ("CH.sub.4")) near5 argon		i .
4	21	near5 (oxygen "O.sub.2")) ((pr photoresist photo?resist (photo near3	USPAT;	2004/09/30 15:08
1	2.1	resist) resist) near10 (etch\$3 pattern4	US-PGPUB	2004/03/30 13:00
		trim\$4 remov\$3) near10 dry ) and	00 10102	
		((hydrocarbon CH4 ("CH.sub.4")) with argon		,
		with (oxygen "O.sub.2"))		
5	5450	(pr photoresist photo?resist (photo near3	EPO; JPO;	2004/09/30 15:12
		resist) resist) near10 (etch\$3 pattern4	DERWENT;	
		trim\$4 remov\$3) near10 dry	IBM_TDB	
6	1	, .F. F Francisco Francisco (Francisco Francisco F	EPO; JPO;	2004/09/30 15:12
		resist) resist) near10 (etch\$3 pattern4	DERWENT;	
		trim\$4 remov\$3) near10 dry ) and ((hydrocarbon CH4 ("CH.sub.4")) and argon	IBM_TDB	
		and oxygen "0.sub.2")		
7	490	1	USPAT;	2004/09/30 15:14
,	1,50	gas) same (oxygen near3 gas)	US-PGPUB	2001, 03, 30 13.11
8	22		USPAT;	2004/09/30 15:15
		gas) same (oxygen near3 gas)) and ((pr	US-PGPUB	,
		photoresist photo?resist (photo near3		
		resist) resist) near10 (etch\$3 pattern4		
		trim\$4 remov\$3))		
-	325112	1 + +	USPAT;	2004/06/21 14:56
_	43155	resist) resist (pr photoresist photo?resist (photo near3	US-PGPUB	2004/06/21 14.56
_	43133	resist) resist) and ((gas plasma) same	USPAT; US-PGPUB	2004/06/21 14:56
		(hydrocarbon oxygen inert))	05-FGF0B	
-	44173		USPAT;	2004/06/21 14:57
		resist) resist) and ((gas plasma) same ((CH4	US-PGPUB	
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar")))		
-	53221		USPAT;	2004/06/21 11:39
		resist) resist) and ((gas plasma) same	US-PGPUB	
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))		
-	33206		USPAT;	2004/06/21 14:57
		resist) resist) and ((gas plasma) same	US-PGPUB	
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)		
_	26375		USPAT;	2004/06/21 11:43
	203.3	resist) resist) and ((gas plasma) same	US-PGPUB	2004/00/21 11.43
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
]		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
		<pre>photo?resist (photo near3 resist) resist) same (etch\$3 pattern4 trim\$4))</pre>		
L	L	same (ecchis paccetha CTIMS4))		

	4.05.05		1	10001/05/03 33 15
-	10795		USPAT;	2004/06/21 11:47
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
	:	same (etch\$3 pattern4 trim\$4))) and ((pr		
	!	photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar")))		
-	6173		USPAT;	2004/06/21 11:45
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	1
		(hydrocarbon oxygen inert))) ((pr		4
		photoresist photo?resist (photo near3		
-		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"0.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
	i	photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3		İ
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4	1	
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
1		"O.sub.2") (argon Ar "Ar")))) and flow		
-	6337	(((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 11:45
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		1
		pattern4 trim\$4)) and ((pr photoresist		1
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		1
		photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
		"O.sub.2") (argon Ar "Ar")))) and (power		
		watt)		
-	7436	1	USPAT;	2004/06/21 11:46
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	, , == ==: 23
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar")))) and pressure		
	L	, (angle in fig. ), (and probbite	J	<u> </u>

-	3924	(((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 11:46
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	
	•	(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		!
		pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3	İ	
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		•
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar")))) and flow) and		
		((((((pr photoresist photo?resist (photo		
		near3 resist) resist) and ((gas plasma) same		
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		•
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	ļ	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	ł	pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr	[	
		photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
		"O.sub.2") (argon Ar "Ar")))) and (power		İ
		watt)) and ((((((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		and ((gas plasma) same (hydrocarbon oxygen		
		inert))) ((pr photoresist photo?resist		
		(photo near3 resist) resist) and ((gas		
		plasma) same ((CH4 "CH.sub.4" ("C" adj3		
		"H.sub.4")) (oxygen 02 "O.sub.2") (argon		
		Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
		and ((pr photoresist photo?resist (photo	1	
		near3 resist) resist) same (etch\$3 pattern4		ĺ
		trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3		
		pattern4 trim\$4)) same ((qas plasma) same		
	]	((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))	-	
		((CH4 "CH.Sub.4" ("C" adj3 "H.Sub.4")) ((oxygen O2 "O.sub.2") (argon Ar "Ar")))) and		
		pressure)		
	1	bressure)	i e	!

- 291	(((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 14:57
	near3 resist) resist) and ((gas plasma) same	US-PGPUB	
	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4	į	
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
]	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
1	pattern4 trim\$4)) and ((pr photoresist		
1	1 -		
	photo?resist (photo near3 resist) resist)		
	same (etch\$3 pattern4 trim\$4))) and ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		,
	"O.sub.2") (argon Ar "Ar")))) and flow) and		
	((((((pr photoresist photo?resist (photo		
	near3 resist) resist) and ((gas plasma) same		
	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
	photo?resist (photo near3 resist) resist)		
	same (etch\$3 pattern4 trim\$4))) and ((pr		
	1		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and (power		
	watt)) and ((((((pr photoresist		
į l	photo?resist (photo near3 resist) resist)		
	and ((gas plasma) same (hydrocarbon oxygen		
	inert))) ((pr photoresist photo?resist		
	(photo near3 resist) resist) and ((gas		
	plasma) same ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) (oxygen 02 "0.sub.2") (argon		
	Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
	and ((pr photoresist photo?resist (photo		
	near3 resist) resist) same (etch\$3 pattern4		
	trim\$4))) and ((pr photoresist photo?resist		İ
	(photo near3 resist) resist) same (etch\$3		
	pattern4 trim\$4)) same ((gas plasma) same		
l İ	((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
	(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and		
	pressure)) and ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) and (oxygen 02 "0.sub.2") and		
	(argon Ar "Ar"))		

-	29	(((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 14:58
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3		,
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		·
		"O.sub.2") (argon Ar "Ar")))) and flow) and		
		(((((((pr photoresist photo?resist (photo		
		near3 resist) resist) and ((qas plasma) same		
		(hydrocarbon oxygen inert))) ((pr		
		photoresist photo?resist (photo near3		
	ł	resist) resist) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
1	ļ	photo?resist (photo near3 resist) resist)		
	i	same (etch\$3 pattern4 trim\$4))) and ((pr		
	i	photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar")))) and (power		
		watt)) and ((((((pr photoresist		
	ļ	photo?resist (photo near3 resist) resist)		
		and ((gas plasma) same (hydrocarbon oxygen		
		<pre>inert))) ((pr photoresist photo?resist</pre>		
		(photo near3 resist) resist) and ((gas		
		plasma) same ((CH4 "CH.sub.4" ("C" adj3		
		"H.sub.4")) (oxygen O2 "O.sub.2") (argon		
		Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
		and ((pr photoresist photo?resist (photo		
		near3 resist) resist) same (etch\$3 pattern4		
		trim\$4))) and ((pr photoresist photo?resist		
		(photo near3 resist) resist) same (etch\$3		ļ
		pattern4 trim\$4)) same ((gas plasma) same		
		((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
		(oxygen O2 "O.sub.2") (argon Ar "Ar")))) and		
		pressure)) and ((C2H6 ("C.sub.2" adj3		
		"H.sub.6")) and (oxygen O2 "O.sub.2") and		
		(argon Ar "Ar"))		

-	44	(((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 14:58
		near3 resist) resist) and ((gas plasma) same	US-PGPUB	
į		(hydrocarbon oxygen inert))) ((pr		
į		photoresist photo?resist (photo near3		
]		resist) resist) and ((gas plasma) same ((CH4		
1		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		l i
1		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
-		photo?resist (photo near3 resist) resist)		
1		same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
		trim\$4)) same ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	}	"O.sub.2") (argon Ar "Ar")))) and flow) and		
		(((((((pr photoresist photo?resist (photo		
	ļ	near3 resist) resist) and ((gas plasma) same	l .	
		(hydrocarbon oxygen inert))) ((pr		
1	Ì	photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same ((CH4		
	1	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
		pattern4 trim\$4)) and ((pr photoresist		
		photo?resist (photo near3 resist) resist)		
		same (etch\$3 pattern4 trim\$4))) and ((pr		
		photoresist photo?resist (photo near3		
		resist) resist) same (etch\$3 pattern4		
	İ	trim\$4)) same ((gas plasma) same ((CH4		
	ļ	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar")))) and (power		
		<pre>watt)) and ((((((pr photoresist</pre>		
	1	photo?resist (photo near3 resist) resist)		
		and ((gas plasma) same (hydrocarbon oxygen		
		<pre>inert))) ((pr photoresist photo?resist</pre>		
		(photo near3 resist) resist) and ((gas		
		plasma) same ((CH4 "CH.sub.4" ("C" adj3		
		"H.sub.4")) (oxygen O2 "O.sub.2") (argon		
		Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
	Į.	and ((pr photoresist photo?resist (photo		
		near3 resist) resist) same (etch\$3 pattern4		
		trim\$4))) and ((pr photoresist photo?resist		
		(photo near3 resist) resist) same (etch\$3		
		pattern4 trim\$4)) same ((gas plasma) same		
		((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
		(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and		
·		pressure)) and ((CHF3 ("CH" adj3		
		"F.sub.3")("C" adj3 "H" adj3 "F.sub.3")) and		
		(oxygen 02 "O.sub.2") and (argon Ar "Ar"))		

- 144	(((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 14:58
	near3 resist) resist) and ((gas plasma) same	US-PGPUB	
	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
	photo?resist (photo near3 resist) resist)		
	same (etch\$3 pattern4 trim\$4))) and ((pr		
	photoresist photo?resist (photo near3		ļ
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and flow) and		
	((((((pr photoresist photo?resist (photo		
	near3 resist) resist) and ((qas plasma) same		
	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
	photo?resist (photo near3 resist) resist)		
	same (etch\$3 pattern4 trim\$4))) and ((pr		1
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and (power		
	watt)) and ((((((pr photoresist		
	photo?resist (photo near3 resist) resist)		
ŀ	and ((gas plasma) same (hydrocarbon oxygen		
	inert))) ((pr photoresist photo?resist		
	(photo near3 resist) resist) and ((qas		
	plasma) same ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) (oxygen 02 "O.sub.2") (argon		
	Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
	and ((pr photoresist photo?resist (photo		
	near3 resist) resist) same (etch\$3 pattern4		
	trim\$4))) and ((pr photoresist photo?resist		
	(photo near3 resist) resist) same (etch\$3		
	pattern4 trim\$4)) same ((qas plasma) same		
	((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
	(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and		
	pressure)) and ((CH2F2 ("CH.sub.2" adj3		
	"F.sub.2") ("C" adj3 "H.sub.2" adj3		
	"F.sub.2")) and (oxygen 02 "0.sub.2") and		
	(argon Ar "Ar"))		
The state of the s	\m-g	i	

- 95	(((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 14:59
į	near3 resist) resist) and ((gas plasma) same	US-PGPUB	
1	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
ļ	resist) resist) and ((gas plasma) same ((CH4		
Ì	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
İ	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
	photo?resist (photo near3 resist) resist)		
	same (etch\$3 pattern4 trim\$4))) and ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and flow) and		
	((((((pr photoresist photo?resist (photo		
	near3 resist) resist) and ((gas plasma) same		
	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
1	resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
	<pre>photo?resist (photo near3 resist) resist)</pre>		
	same (etch\$3 pattern4 trim\$4))) and ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and (power		
	<pre>watt)) and ((((((pr photoresist</pre>		
	<pre>photo?resist (photo near3 resist) resist)</pre>		
	and ((gas plasma) same (hydrocarbon oxygen	İ	
	<pre>inert))) ((pr photoresist photo?resist</pre>		
	(photo near3 resist) resist) and ((gas		
	plasma) same ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) (oxygen 02 "O.sub.2") (argon		
1	Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
	and ((pr photoresist photo?resist (photo		
	near3 resist) resist) same (etch\$3 pattern4		
	trim\$4))) and ((pr photoresist photo?resist	1	
	(photo near3 resist) resist) same (etch\$3		
	pattern4 trim\$4)) same ((gas plasma) same		
	((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
	(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and		
	pressure)) and ((CH3F ("CH.sub.3" adj3		
	"F")("C" adj3 "H.sub.3" adj3 "F")) and		
1	(oxygen 02 "O.sub.2") and (argon Ar "Ar"))		

-   11	(((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 14:59
	near3 resist) resist) and ((gas plasma) same	US-PGPUB	
i i	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
	photo?resist (photo near3 resist) resist)		
	same (etch\$3 pattern4 trim\$4))) and ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and flow) and		
	(((((((pr photoresist photo?resist (photo		
	near3 resist) resist) and ((gas plasma) same		
	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	<pre>pattern4 trim\$4)) and ((pr photoresist</pre>		
	<pre>photo?resist (photo near3 resist) resist)</pre>		
	<pre>same (etch\$3 pattern4 trim\$4))) and ((pr</pre>		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and (power		·
	watt)) and ((((((pr photoresist		
	photo?resist (photo near3 resist) resist)		
	and ((qas plasma) same (hydrocarbon oxygen		
	inert))) ((pr photoresist photo?resist		
	(photo near3 resist) resist) and ((qas		
	plasma) same ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) (oxygen 02 "0.sub.2") (argon		
	13		
	Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
	and ((pr photoresist photo?resist (photo		
	near3 resist) resist) same (etch\$3 pattern4		
	trim\$4))) and ((pr photoresist photo?resist		
	(photo near3 resist) resist) same (etch\$3		
	pattern4 trim\$4)) same ((gas plasma) same		
	((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
	(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and		
	pressure)) and ((C2H2F4 ("C.sub.2" adj3		
	"H.sub.2" adj3 "F.sub.4")) and (oxygen O2		
	"O.sub.2") and (argon Ar "Ar"))		

		T	10001/05/01 11 50
-   4	(((((((((pr photoresist photo?resist (photo	USPAT;	2004/06/21 11:58
	near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr	US-PGPUB	
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4	!	
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3		
	pattern4 trim\$4)) and ((pr photoresist		
	<pre>photo?resist (photo near3 resist) resist)</pre>		
	same (etch\$3 pattern4 trim\$4))) and ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4   "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and flow) and		
	((((((pr photoresist photo?resist (photo		
	near3 resist) resist) and ((gas plasma) same		
	(hydrocarbon oxygen inert))) ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"0.sub.2") (argon Ar "Ar"))))) and (etch\$3 pattern4 trim\$4)) and ((pr photoresist		
	photo?resist (photo near3 resist) resist)		
	same (etch\$3 pattern4 trim\$4))) and ((pr		
	photoresist photo?resist (photo near3		
	resist) resist) same (etch\$3 pattern4		
	trim\$4)) same ((gas plasma) same ((CH4	ł	
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
	"O.sub.2") (argon Ar "Ar")))) and (power		
	<pre>watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist)</pre>		
	and ((gas plasma) same (hydrocarbon oxygen		
	inert))) ((pr photoresist photo?resist		1
	(photo near3 resist) resist) and ((gas		
	plasma) same ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) (oxygen O2 "O.sub.2") (argon		
	Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
	and ((pr photoresist photo?resist (photo		
	near3 resist) resist) same (etch\$3 pattern4		
	trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3		
	pattern4 trim\$4)) same ((gas plasma) same		
	((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
	(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and		
	pressure)) and ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) and (oxygen O2 "O.sub.2") and		
	(argon Ar "Ar"))) ((((((((pr photoresist		
	photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen		
	inert))) ((pr photoresist photo?resist		
	(photo near3 resist) resist) and ((gas		
	plasma) same ((CH4 "CH.sub.4" ("C" adj3		
	"H.sub.4")) (oxygen O2 "O.sub.2") (argon		
	Ar "Ar"))))) and (etch\$3 pattern4 trim\$4))		
	and ((pr photoresist photo?resist (photo		
	near3 resist) resist) same (etch\$3 pattern4		
	trim\$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch\$3		
	pattern4 trim\$4)) same ((qas plasma) same		
	((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))	1	
	(oxygen 02 "0.sub.2") (argon Ar "Ar")))) and	]	
	flow) and ((((((pr photoresist photo?resist	1	
	(photo near3 resist) resist) and ((gas		
	plasma) same (hydrocarbon oxygen inert)))	1	
	((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4		
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
	"O.sub.2") (argon Ar "Ar"))))) and (etch\$3	1	
	pattern4 trim\$4)) and ((pr photoresist	1	
	<pre>photo?resist (photo near3 resist) resist)</pre>		
	same (etch\$3 pattern4 trim\$4))) and ((pr	1	
Search History	9/photoresist photoresist (photo near3 resist) resist) same (etch\$3 pattern4	<del> </del>	<del>   </del>
1 -	resist) resist) same (etch\$3 pattern4 (spaqes m\$9665984mevsp(gas plasma) same ((CH4	1	
	"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen 02		
1	The state of the s	I	

-	200756	pr photoresist photo?resist (photo near3 resist) resist	EPO; JPO; DERWENT; IBM TDB	2004/06/21 14:56
-	5332	(pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same	EPO; JPO; DERWENT;	2004/06/21 14:56
_	4328	<pre>(hydrocarbon oxygen inert)) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same</pre>	IBM_TDB EPO; JPO; DERWENT;	2004/06/21 14:57
		(hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3	IBM_TDB	
		"H.sub.4")) (oxygen O2 "O.sub.2") (argon   Ar "Ar")))		
-	2710		EPO; JPO; DERWENT;	2004/06/21 14:57
		(hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3	IBM_TDB	
		"H.sub.4")) (oxygen O2 "O.sub.2") (argon		
-	2		EPO; JPO;	2004/06/21 14:58
		resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas	DERWENT; IBM TDB	
		plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon	_	
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4))		
		and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen 02 "O.sub.2") and (argon Ar		
_	2	<pre>"Ar")) ((((pr photoresist photo?resist (photo near3</pre>	EPO; JPO;	2004/06/21 14:58
		resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas	DERWENT; IBM TDB	
		plasma) same ((CH4 "CH.sub.4" ("C" adj3	13133	
		"H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))) and (etch\$3 pattern4 trim\$4))		
		and ((C2H6 ("C.sub.2" adj3 "H.sub.6")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))		
-	6	<pre>(((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same</pre>	EPO; JPO; DERWENT;	2004/06/21 14:58
		(hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3	IBM_TDB	
		"H.sub.4")) (oxygen 02 "O.sub.2") (argon		
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((CHF3 ("CH" adj3 "F.sub.3")("C" adj3		
		"H" adj3 "F.sub.3")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))		
-	2		EPO; JPO; DERWENT;	2004/06/21 14:59
		(hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3	IBM_TDB	
		"H.sub.4")) (oxygen 02 "O.sub.2") (argon		
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((CH2F2 ("CH.sub.2" adj3 "F.sub.2")("C"		
		adj3 "H.sub.2" adj3 "F.sub.2")) and (oxygen   O2 "O.sub.2") and (argon Ar "Ar"))		
-	1		EPO; JPO; DERWENT;	2004/06/21 14:59
		(hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3	IBM_TDB	
		"H.sub.4")) (oxygen 02 "O.sub.2") (argon		
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((CH3F ("CH.sub.3" adj3 "F")("C" adj3		
		"H.sub.3" adj3 "F")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))		
-	0	<pre>(((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same</pre>	EPO; JPO; DERWENT;	2004/06/21 14:59
		(hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3	IBM_TDB	
		"H.sub.4")) (oxygen O2 "O.sub.2") (argon		
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((C2H2F4 ("C.sub.2" adj3 "H.sub.2" adj3		
		"F.sub.4")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))		

Page 11

-	9	(((((pr photoresist photo?resist (photo	EPO; JPO;	2004/06/21 15:00
Į		near3 resist) resist) and ((gas plasma) same	DERWENT;	
		(hydrocarbon oxygen inert))) and ((gas	IBM_TDB	
ļ		plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon		
1		Ar "Ar")))) and (etch\$3 pattern4 trim\$4))		
		and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4"))		
		and (oxygen 02 "O.sub.2") and (argon Ar		
		"Ar"))) (((((pr photoresist photo?resist		
		(photo near3 resist) resist) and ((gas		
		plasma) same (hydrocarbon oxygen inert)))		
		and ((gas plasma) same ((CH4 "CH.sub.4" ("C"		
		adj3 "H.sub.4")) (oxygen O2 "O.sub.2")		
		(argon Ar "Ar")))) and (etch\$3 pattern4		
	}	trim\$4)) and ((C2H6 ("C.sub.2" adj3		
		"H.sub.6")) and (oxygen 02 "O.sub.2") and		
		(argon Ar "Ar"))) (((((pr photoresist photo?resist (photo near3 resist) resist)		
		and ((gas plasma) same (hydrocarbon oxygen	· ·	
	İ	inert))) and ((gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2		
		"O.sub.2") (argon Ar "Ar")))) and (etch\$3		
		pattern4 trim\$4)) and ((CHF3 ("CH" adj3		
		"F.sub.3")("C" adj3 "H" adj3 "F.sub.3")) and		
		(oxygen O2 "O.sub.2") and (argon Ar "Ar")))		
		(((((pr photoresist photo?resist (photo		
		near3 resist) resist) and ((gas plasma) same		
		(hydrocarbon oxygen inert))) and ((gas		
		plasma) same ((CH4 "CH.sub.4" ("C" adj3		
		"H.sub.4")) (oxygen O2 "O.sub.2") (argon		
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4)) and ((CH2F2 ("CH.sub.2" adj3 "F.sub.2")("C"		
		adj3 "H.sub.2" adj3 "F.sub.2")) and (oxygen		
		02 "0.sub.2") and (argon Ar "Ar"))) (((((pr		
		photoresist photo?resist (photo near3		
		resist) resist) and ((gas plasma) same		
		(hydrocarbon oxygen inert))) and ((gas		
		plasma) same ((CH4 "CH.sub.4" ("C" adj3		
		"H.sub.4")) (oxygen 02 "O.sub.2") (argon		
		Ar "Ar")))) and (etch\$3 pattern4 trim\$4))		
		and ((CH3F ("CH.sub.3" adj3 "F")("C" adj3   "H.sub.3" adj3 "F")) and (oxygen O2		
		"O.sub.2") and (argon Ar "Ar")))		
_	325112	l	USPAT;	2004/06/21 16:43
	020222	resist) resist	US-PGPUB	
_	11384	thin\$4 near5 (pr photoresist photo?resist	USPAT;	2004/06/21 15:53
	i	(photo near3 resist) resist)	US-PGPUB	
-	20039		USPAT;	2004/06/21 15:53
		(photo near3 resist) resist)	US-PGPUB	
-	10479		USPAT;	2004/06/21 15:54
		(photo near3 resist) resist)) and (etch\$3	US-PGPUB	
_	1618	trim\$4 pattern\$4) ((thin\$4 near5 (pr photoresist photo?resist	USPAT;	2004/06/21 16:07
	1010	(photo near3 resist) resist)) and (etch\$3	US-PGPUB	2007/00/21 10:0/
		trim\$4 pattern\$4)) and ((argon Ar) and	35 13705	
		(oxygen 02 "0.sub.2"))	1	
-	337	(((thin\$4 near5 (pr photoresist photo?resist	USPAT;	2004/06/21 15:56
		(photo near3 resist) resist)) and (etch\$3	US-PGPUB	
]		trim\$4 pattern\$4)) and ((argon Ar) and		
		(oxygen 02 "0.sub.2"))) and (CHF3		
	105	"CHF.sub.3" ("C" adj3 "H" adj3 "F.sub.3"))	I I CD T T	2004/05/22 25 55
-	405	1 '* *	USPAT;	2004/06/21 16:06
_	105	resist) resist) and (micro near3 load\$3) ((pr photoresist photo?resist (photo near3	US-PGPUB USPAT;	2004/06/21 16:43
	103	resist) resist) and (micro near3 load\$3))	US-PGPUB	2004/00/21 10:43
		and ((argon Ar) and (oxygen 02 "O.sub.2"))	35 7 37 05	
-	200756		EPO; JPO;	2004/06/21 16:43
		resist) resist	DERWENT;	
			IBM_TDB	
-	517	'	EPO; JPO;	2004/06/21 16:43
		resist) resist) and ((argon Ar) and (oxygen	DERWENT;	
L		02 "0.sub.2"))	IBM_TDB	

-	3	((pr photoresist photo?resist (photo near3	EPO; JPO;	2004/06/21 16:44
	•	resist) resist) and ((argon Ar) and (oxygen	DERWENT;	
		O2 "O.sub.2"))) and (micro near3 load\$3)	IBM_TDB	
-	919	(pr photoresist photo?resist (photo near3	USPAT;	2004/09/30 14:31
		resist) resist) and (etch\$3 pattern4	US-PGPUB	
		trim\$4) and (gas plasma) and ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen		
		02 "0.sub.2") and (argon Ar "Ar"))		
-	63		USPAT;	2004/09/30 14:36
		resist) resist) and (etch\$3 pattern4	US-PGPUB	
		trim\$4) and (gas plasma) and ((CH4		
1		"CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen		
		02 "0.sub.2") and (argon Ar "Ar"))) and		
}		(critical near3 dimens\$3)		
_	39	1 -	USPAT;	2004/09/30 14:20
		resist) resist) same (etch\$3 pattern4	US-PGPUB	=====================================
		trim\$4) and (gas plasma) same ((CH4	05 10105	
		"CH.sub.4" ("C" adj3 "H.sub.4") hydrocarbon)		
		same (oxygen O2 "O.sub.2") same (argon Ar		
		"Ar"))) and (critical near3 dimens\$3)		
_	3		EPO; JPO;	2004/09/30 14:37
		resist) resist) and (etch\$3 pattern4	DERWENT;	2004/03/30 14.37
		trim\$4) and (gas plasma) and ((CH4	IBM TDB	
		"CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen	1511_105	
		O2 "O.sub.2") and (argon Ar "Ar"))		
_	81834		EPO; JPO;	2004/09/30 14:36
_	01034	(CD (CITCICAL HEALS CIMEHS\$3))	DERWENT:	2004/09/30 14:36
			IBM TDB	
	1637	((CD (critical near3 dimens\$3))) and (pr	EPO; JPO;	2004/09/30 14:37
-	1637	photoresist photo?resist (photo near3	DERWENT;	2004/09/30 14:37
		resist) resist)		
_	769	· · · · · · · · · · · · · · · · · · ·	IBM_TDB	2004/00/20 34 43
-	'69	((( (	EPO; JPO;	2004/09/30 14:41
		photoresist photo?resist (photo near3	DERWENT;	
		resist) resist) ) and (pattern\$4 etch\$3	IBM_TDB	1
	200	trim\$4)		0001/00/00 1: :-
-	304	, the barrenger busys the the	USPAT;	2004/09/30 14:43
		resist) resist) same (etch\$3 pattern4	US-PGPUB	}
		trim\$4) and (gas plasma) same ((CH4		
		"CH.sub.4" ("C" adj3 "H.sub.4") hydrocarbon)		
		same (oxygen O2 "O.sub.2") same (argon Ar		
	l	"Ar"))		l